

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	METHOD FOR REACTIVE ION ETCH PROCESSING OF A DUAL DAMASCENE STRUCTURE
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Application Number : 10/709,630

Confirmation Number:

First Named Applicant: William America

Attorney Docket Number: FIS920040053US1

Art Unit: 2825

Examiner: B. KESHAVAN

Search string: ( 6479391 or 6514852 or 6573176 or 6576482 ).pn

## US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
PK	1	6479391	2002-11-12	Morrow et al	—	—	—
BK	2	6514852	2003-02-04	Usami	—	—	—
BK	3	6573176	2003-06-03	Hong	—	—	—
BK	4	6576482	2003-06-10	Aggarwal et al	—	—	—

Signature



11/22/2004

Examiner Name	Date
B. KESHAVAN	11/22/2004

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.